



Attorney Docket No.: CYPR-  
CD01175M

**IN THE UNITED STATES PATENT AND TRADEMARK OFFICE**  
Patent Application

Inventor(s): Ogami et al.

Group Art Unit: 2123

Filed: November 19, 2001

Examiner: Osborne, L.

Application No.: 09/989,762

Title: SYSTEM AND METHOD FOR PERFORMING NEXT PLACEMENTS AND PRUNING OF  
DISALLOWED PLACEMENTS FOR PROGRAMMING AN INTEGRATED CIRCUIT

Form 1449

**U.S. Patent Documents**

Examiner Initial	No.	Patent No.	Date	Patentee	Class	Sub-class	Filing Date
	A	2002/0085020	07-04-2002	Carroll Jr.			
	B	4,942,540	07-17-1990	Black et al.			
	C	5,381,524	01-10-1995	Lewis et al.			
	D	5,394,522	02-28-1995	Sanchez-Frank et al.			
	E	5,732,277	03-24-1998	Kodosky et al.			
	F	5,818,444	10-06-1998	Alimpich et al.			
	G	5,819,028	10-06-1998	Manghirmalani et al.			
	H	5,867,399	02-02-1999	Rostoker et al.			
	I	5,930,150	07-27-1999	Cohen et al.			
	J	5,933,356	08-03-1999	Rostoker et al.			
	K	5,941,991	08-24-1999	Kageshima			
	L	5,988,902	11-23-1999	Holehan			
	M	6,110,223	08-29-2000	Southgate et al.			
	N	6,246,410	06-12-2001	Bergeron et al.			
	O	6,321,369	11-20-2001	Heile et al.			
	P	6,366,300	04-02-2002	Ohara et al.			
	Q	6,388,109	05-14-2002	Schwarz et al.			
	R	6,417,872	07-09-2002	Zimmerman et al.			
	S	6,438,738	08-20-2002	Elayda			
	T	6,457,479	10-01-2002	Zhuang et al.			
	U	6,516,452	02-04-2003	Meding			
	V	6,530,065	03-04-2003	McDonald et al.			
	W	6,557,149	04-29-2003	Morrise et al.			
	X	6,571,331	05-27-2003	Henry et al.			
	Y	6,594,799	07-15-2003	Chiang et al.			
	Z	6,606,731	08-12-2003	Baum et al.			
	A1	6,750,889	06-15-2004	Livingston et al.			

**Foreign Patent or Published Foreign Patent Application**

Examiner Initial	No.	Document No.	Publication Date	Country or Patent Office	Class	Sub-class	Translation	
							Yes	No
	B1							
	C1							
	D1							

**Other Documents**

Examiner Initial	No.	Author, Title, Date, Place (e.g. Journal) of Publication
	E1	"PSoc Designer: Integrated Development Environment"; May 30, 2001; Cypress Microsystems, Inc.

	F1	
	G1	
Examiner		Date Considered

Examiner: Initial citation considered. Draw line through citation if not in conformance and not considered.  
 Include copy of this form with next communication to applicant.